

ABSTRACT OF THE DISCLOSURE

- A method of using PFCs recovered from the effluent of a CVD chamber cleaning
- 5 process as an influent for the cleaning process is provided which includes the steps of selecting a first PFC gas mixture having a first ratio of C_2F_6 to CF_4 , providing the first PFC gas mixture as the influent gas to the CVD chamber to create a CVD chamber effluent gas of a second PFC gas mixture having a second ratio of C_2F_6 to CF_4 , adding virgin C_2F_6 or CF_4 to the CVD chamber effluent gas in sufficient quantity to create a third
- 10 PFC gas mixture having the first ratio of C_2F_6 to CF_4 , and using the third PFC gas mixture as the influent gas to the CVD chamber.

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